

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	3438	(wafer or semiconductor or substrate) and (cleaning or processing or drying or development or etching or rinsing) and (supercritical or subcritical) and (carbon near2 dioxide) and pressure	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/08 16:38
S2	890	(wafer or semiconductor or substrate) and (cleaning or processing or drying or development or etching or rinsing) and (supercritical or subcritical) with (carbon near2 dioxide) with pressure	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/08 16:38
S3	522	(wafer or semiconductor or substrate) and (cleaning or processing or drying or development or etching or rinsing) and ((supercritical or subcritical) with (carbon near2 dioxide) with pressure) and (rotate or rotat\$4 or rotational or spin or spinning or revolve or revolving or turn or turning)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/08 17:37
S4	491	(wafer or semiconductor or substrate) and (cleaning or processing or drying or development or etching or rinsing) and ((supercritical or subcritical) with (carbon near2 dioxide)) and (rotate or rotat\$4 or rotational or spin or spinning or revolve or revolving or turn or turning) and (high-pressure)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/08 16:48
S5	1135	(wafer or semiconductor or substrate) and (cleaning or processing or drying or development or etching or rinsing) and ((supercritical or subcritical) with (carbon near2 dioxide)) and (rotate or rotat\$4 or rotational or spin or spinning or revolve or revolving or turn or turning) and ((high near2 pressure) or (high-pressure))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/08 17:19

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S6	1135	(wafer or semiconductor or substrate) and (cleaning or processing or drying or development or etching or rinsing) and ((supercritical or subcritical) with (carbon near2 dioxide)) and (rotate or rotat\$4 or rotational or spin or spinning or revolve or revolving or turn or turning) and ((high near2 pressure))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/08 17:10
S7	20	("4197000" "5037506" "5226242" "5238773" "5279921" "5286599" "5457005" "5707487" "5718763" "5763016" "5783367" "5881750" "5908510" "5954911" "6033134" "6056026" "6199604" "6276378" "6629539" "6660460").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2007/12/08 17:10
S8	1613	(wafer or semiconductor or substrate) and (cleaning or processing or drying or development or etching or rinsing) and ((supercritical or subcritical) with (fluid)) and (rotate or rotat\$4 or rotational or spin or spinning or revolve or revolving or turn or turning) and ((high near2 pressure) or (high-pressure))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/08 17:19
S9	24346	(wafer or semiconductor or substrate) and (cleaning or processing or drying or development or etching or rinsing) and ((supercritical or subcritical) with (carbon near2 dioxide) or (fluid)) and (rotate or rotat\$4 or rotational or spin or spinning or revolve or revolving or turn or turning) and ((high near2 pressure) or (high-pressure))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/08 17:25
S10	1787	(wafer or semiconductor or substrate) and (cleaning or processing or drying or development or etching or rinsing) and ((supercritical or subcritical) with ((carbon near2 dioxide) or (fluid))) and (rotate or rotat\$4 or rotational or spin or spinning or revolve or revolving or turn or turning) and ((high near2 pressure) or (high-pressure))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/08 17:33

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S11	43	(wafer or semiconductor or substrate) and (cleaning or processing or drying or development or etching or rinsing) and ((supercritical or subcritical) with ((carbon near2 dioxide) or (fluid))) and (rotate or rotat\$4 or rotational or spin or spinning or revolve or revolving or turn or turning) and ((high near2 pressure) or (high-pressure)) and chamber and shower	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/08 17:27
S12	0	("7252719").URPN.	USPAT	OR	OFF	2007/12/08 17:30
S13	20	("4197000" "5037506" "5226242" "5238773" "5279921" "5286599" "5457005" "5707487" "5718763" "5763016" "5783367" "5881750" "5908510" "5954911" "6033134" "6056026" "6199604" "6276378" "6629539" "6660460").PN. OR ("7252719").URPN.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/12/08 17:30
S14	182	(wafer or semiconductor or substrate) and "134".clas. and ((supercritical or subcritical) with ((carbon near2 dioxide) or (fluid))) and (rotate or rotat\$4 or rotational or spin or spinning or revolve or revolving or turn or turning) and ((high near2 pressure) or (high-pressure))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/08 17:36
S15	6	((wafer or semiconductor or substrate) with (cleaning or drying)).ab. and ((supercritical or subcritical) with ((carbon near2 dioxide) or (fluid))) and (rotate or rotat\$4 or rotational or spin or spinning or revolve or revolving or turn or turning) and ((high near2 pressure) or (high-pressure))	EPO; JPO; DERWENT	OR	ON	2007/12/08 17:47
S16	188	S14 or S15	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/08 17:45
S17	1	("6730612").PN.	USPAT; USOCR	OR	OFF	2007/12/08 17:45

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S18	24	("3987963" "5482564" "5494526" "5514220" "5522938" "5700379" "5779796" "5865901" "5866005" "5868856" "5868862" "5922833" "5944996" "5976264" "6001418" "6024801" "6030663" "6059893" "6067728" "6103096" "6149828" "6240936" "6242165" "6277753").PN. OR ("6730612").URPN.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/12/08 17:45
S19	40	("4640846" "4794021" "4886012" "4944837" "5094892" "5264246" "5392989" "5455076" "5466490" "5472502" "5494526" "5496901" "5591264" "5665527" "5989355").PN. OR ("6240936").URPN.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/12/08 17:46
S20	0	((wafer or semiconductor or substrate) with (drying)).ab. and ((supercritical or subcritical) with ((carbon near2 dioxide) or (fluid))) and (rotate or rotat\$4 or rotational or spin or spinning or revolve or revolving or turn or turning) and ((high near2 pressure) or (high-pressure))	EPO; JPO; DERWENT	OR	ON	2007/12/08 17:47
S21	36	((wafer or semiconductor or substrate) with (drying)).ab. and ((supercritical or subcritical) with ((carbon near2 dioxide) or (fluid))) and (rotate or rotat\$4 or rotational or spin or spinning or revolve or revolving or turn or turning) and ((high near2 pressure) or (high-pressure))	US-PGPUB; USPAT; USOCR	OR	ON	2007/12/08 19:04
S22	3231	(wafer or semiconductor or substrate) and "134".clas. and (shower or nozzle)	US-PGPUB; USPAT; USOCR	OR	ON	2007/12/08 19:24
S23	2781	(wafer or semiconductor or substrate) and "134".clas. and (shower or nozzle) and cleaning	US-PGPUB; USPAT; USOCR	OR	ON	2007/12/08 19:05
S24	416	(wafer or semiconductor or substrate) and "134".clas. and (shower) and cleaning	US-PGPUB; USPAT; USOCR	OR	ON	2007/12/08 19:11
S25	1	("7172657").PN.	USPAT; USOCR	OR	OFF	2007/12/08 19:11
S26	381	(wafer or semiconductor or substrate) and (supercritical) and (drying or drier or cleaning)	EPO; JPO; DERWENT	OR	ON	2007/12/08 19:25

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S27	87	("4341592").PN. OR ("4944837"). URPN.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/12/08 19:39
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S28	201	("20020001929" "2617719" "2625886" "3744660" "3968885" "4029517" "4091643" "4245154" "4341592" "4355937" "4367140" "4406596" "4422651" "4474199" "4522788" "4549467" "4592306" "4601181" "4626509" "4670126" "4682937" "4693777" "4749440" "4778356" "4788043" "4789077" "4823976" "4825808" "4827867" "4838476" "4865061" "4879431" "4917556" "4924892" "4944837" "4951601" "4960140" "4983223" "5011542" "5013366" "5044871" "5062770" "5068040" "5071485" "5105556" "5143103" "5167716" "5169296" "5169408" "5185296" "5186718" "5188515" "5190373" "5191993" "5193560" "5195878" "5213485" "5213619" "5215592" "5217043" "5221019" "5222876" "5224504" "5236602" "5236669" "5237824" "5240390" "5243821" "5246500" "5251776" "5267455" "5280693" "5285352" "5288333" "5304515" "5306350" "5313965" "5314574" "5316591" "5328722" "5337446" "5339844" "5355901" "5368171" "5370740" "5370741" "5377705" "5401322" "5403621" "5404894" "5412958" "5417768" "5433334" "5447294" "5456759" "5494526" "5500081" "5501761" "5503176" "5505219" "5509431" "5522938" "5526834" "5533538" "5571330" "5589224" "5621982" "5629918" "5644855" "5649809" "5656097" "5669251" "5672204" "5683977" "5702228" "5706319" "5746008" "5797719" "5798126" "5817178" "5868856" "5868862" "5881577" "5882165").PN. OR ("5888050" "5898727" "5900107" "5900354" "5904737" "5908510" "5928389" "5932100" "5934991" "5955140" "5976264" "5979306" "5980648" "5981399" "5989342" "6005226" "6017820" "6024801" "6029371" "6035871" "6037777" "6053348" "6056008"	US-PGPUB; USPAT; USOCR	OR	OFF	2007/12/08 20:03
12/9/2007 4:18:22 PM		C:\Documents and Settings\Tingaleman\My Documents\EAST\Workspaces\10688889.wsp				Page 6

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S29	1	("6647993").PN.	USPAT; USOCR	OR	OFF	2007/12/08 20:03
S30	7	("4813326" "5397432" "5581874" "5788778" "5900103" "6143084").PN. OR ("6647993"). URPN.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/12/08 20:03